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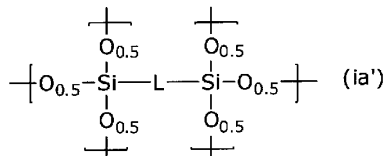
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(54) Title: PHOTSENSITIVE SILOXANE COMPOSITION AND PATTERN FORMING METHOD USING THE SAME



(57) Abstract: To provide a photosensitive siloxane composition capable of forming a pattern having a desired taper angle and a desired linewidth. [Means] The present invention provides a photosensitive siloxane composition comprising : a polysiloxane having a structure represented by the following formula (ia') : (L is an alkylene or phenylene), a photoactive agent, and a solvent.



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